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	Application No.	Applicant(s)	
N = (* 5 A H   + 1   4 -	10/654,979	HIGUCHI, KENICHI	
Notice of Allowability	Examiner	Art Unit	
	George A. Goudreau	1763	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in this ap i) or other appropriate communication RIGHTS. This application is subject to	plication. If not include will be mailed in due	ed course. <b>THIS</b>
1. This communication is responsive to papers filed on (9-5-	<u>03' to 4-28-04')</u> .		
2. The allowed claim(s) is/are <u>1-18</u> .			
3. $\boxtimes$ The drawings filed on <u>05 September 2003</u> are accepted b	y the Examiner.		
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority of a)  All b)  Some* c)  None of the:  1.  Certified copies of the priority documents have  2.  Certified copies of the priority documents have  3.  Copies of the certified copies of the priority documents have  International Bureau (PCT Rule 17.2(a)).  * Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDON'THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.</li> <li>5.  A SUBSTITUTE OATH OR DECLARATION must be submin INFORMAL PATENT APPLICATION (PTO-152) which give 6.  CORRECTED DRAWINGS (as "replacement sheets") must  (a)  including changes required by the Notice of Draftsper  1)  hereto or 2)  to Paper No./Mail Date  (b)  including changes required by the attached Examiner Paper No./Mail Date  Identifying indicia such as the application number (see 37 CFR reach sheet. Replacement sheet(s) should be labeled as such in the such as the subminimal priority of the stacked as such in the sheet. Replacement sheet(s) should be labeled as such in the such as the application number (see 37 CFR reach sheet. Replacement sheet(s) should be labeled as such in the such as the application number (see 37 CFR reach sheet. Replacement sheet(s) should be labeled as such in the such as the application number (see 37 CFR reach sheet. Replacement sheet(s) should be labeled as such in the such as the application number (see 37 CFR reach sheet. Replacement sheet(s) should be labeled as such in the such as the application number (see 37 CFR reach sheet. Replacement sheet(s) should be labeled as such in the such as the application number (see 37 CFR reach sheet. Replacement sheet(s) should be labeled as such in the such as the su</li></ul>	re been received. re been received in Application No cocuments have been received in this representation to file a reply MENT of this application.  Initted. Note the attached EXAMINER res reason(s) why the oath or declarates the submitted. It is a part of the submitted of the submitted. It is a part of the submitted of the s	national stage applicate complying with the requestion is deficient.  948) attached office action of the front (not the	juirements OTICE OF
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT			lote the
Attachment(s)  1. ☑ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date  4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. ☐ Notice of Informal P 6. ☐ Interview Summary Paper No./Mail Dat 7. ☐ Examiner's Amendr 8. ☑ Examiner's Stateme 9. ☐ Other	(PTO-413), te nent/Comment ent of Reasons for Allow	·
		george gou	DREAU

PRIMARY EXAMINE

Application/Control Number: 10/654,979

Art Unit: 1763

1. Claims 1-18 are allowed.

The following is an examiner's statement of reasons for allowance:

-The prior art of record fails to either singularly or collectively disclose a process for rie etching an organic insulating film on a substrate using a plasma which is comprised of NH3 in a parallel plate etcher in which the cathode is biased with an RF power source of a first frequency, and the anode is biased with an RF power source of a second frequency, wherein the first frequency is different from the second frequency.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

- 2. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.
- 3. Any inquiry concerning this communication should be directed to examiner George A. Goudreau at telephone number (571)-272-1434.

George A. Goudre

Art Unit 1763